



LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT (use several sheets if necessary)		SERIAL NO. 10/680,509	CASE NO. 10322/57
		FILING DATE October 7, 2003	GROUP ART UNIT 2814
		APPLICANT(S): Kuang Chien et al.	

REFERENCE DESIGNATION
U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER <small>Number-Kind Code (if known)</small>	DATE	NAME	CLASS/ SUBCLASS	FILING DATE
WZ	B1	5,920,766	July 6, 1999	Floyd		
	B2	5,858,855	January 12, 1999	Kobayashi		
	B3	5,854,090	December 29, 1998	Iwai et al.		
	B4	5,233,216	August 3, 1993	Inoue et al.		

FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER <small>Number-Kind Code (if known)</small>	DATE	COUNTRY	CLASS/ SUBCLASS	TRANSLATION YES OR NO
WZ	B5	EP 1 246 238 A2	October 2, 2002	EPO		
	B6	JP 10-12506	January 16, 1998	Japan		

EXAMINER INITIAL	OTHER ART - NON PATENT LITERATURE DOCUMENTS	
	(Include name of author, title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date page(s), volume-issue number(s), publisher, city and/or country where published.)	
WZ	B7	Copy of International Search Report from corresponding PCT patent application number PCT/US2004/031254.
	B8	K.L. Chang, G.W. Pickrell, K.Y. Cheng and K.C. Hsieh, <i>Wafer Bonding With Low-Temperature-Grown (Ga,P) as an Adhesive Material</i> , pgs. 906-910, Institute of Physics Publishing, Semiconductor Science and Technology, 2004
	B9	K.D. Choquette, K.M. Geib, B. Roberds, H.Q. Hou, R.D. Tweten and B.E. Hammons, <i>Short Wavelength Bottom-Emitting Vertical Cavity Lasers Fabricated Using Wafer Bonding</i> , pgs. 1404-1405, IEEE, Electronic Letters, Vol. 34, No. 14, July 9, 1998.
	B10	K. Mori, K. Tokutome and S. Sugou, <i>Low-Threshold Pulsed Operation of Long-wavelength Lasers on Si Fabricated By Direct Bonding</i> , pgs. 284-285, IEEE Electronic Letters, Vol. 31, No. 4, February 16, 1995.

EXAMINER	Vilhi Trich	DATE CONSIDERED	01/12/06
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.